

PROCEEDINGS

Developing Two-Wavelength Digital Light Processing-Based Vat Photopolymerization for Multi-Material/High-Resolution 3D Printing

Xiayun Zhao^{1*}, Yue Zhang¹, Heyang Zhang¹, Yousra Bensouda¹, Md Jahangir Alam¹, Haolin Zhang¹ and Yiquan Wang¹

¹Department of Mechanical Engineering and Materials Science, University of Pittsburgh, Pittsburgh, Pennsylvania, 15261, USA

*Corresponding Author: Xiayun Zhao. Email: xiayun.zhao@pitt.edu

ABSTRACT

Vat photopolymerization (VPP) among other additive manufacturing (AM) processes have a great potential to rapidly print complex 3D components out of a matrix of photo-curable resin. Current VPP processes utilize single-wavelength light exposure, imposing limitations on print speed and throughput, especially in multi-material AM. This is attributed to delays in material switch-over mechanisms. Additionally, the resolution of conventional single-wavelength VPP is constrained by over-curing. Despite ongoing efforts and progress in VPP, there remains a need for effective approaches to address these persistent issues.

In this work, we report our development of two-wavelength digital light processing-based VPP processes, denoted as VPP_{2λ}. Generally, the VPP_{2λ} process involves concurrent light irradiation at two different wavelengths, inducing distinct photochemical reactions. This allows for spatial modulation of material processing, achieving localized composition and properties. Our research lab is investigating two types of VPP_{2λ} processes tailored for two critical application scenarios: 1) rapid, continuous, and complexly architected multi-material VPP; and 2) high-accuracy, high-resolution precision VPP. The first process, specifically designed for multi-material (Mm) AM, is referred to as two-wavelength selective VPP (MmVPP_{2λ}). MmVPP_{2λ} employs two-wavelength light patterns to selectively cure different material components at different locations within each layer. This enables the continuous construction of real 3D multi-material parts without the need to change vats. The second process, termed photoinhibition-aided VPP_{2λ} (PinVPP_{2λ}), utilizes two-wavelength exposure masks for initiating and inhibiting polymerization. PinVPP_{2λ} is designed to address both vertical and lateral over-curing issues, thereby enhancing not only print speed but also three-dimensional accuracy, resolution, and precision.

This work presents fundamental and experimental research aimed at establishing the feasibility and enhancing the performance of the MmVPP_{2λ} and PinVPP_{2λ} processes. Physics-based data-driven modeling methods [1; 2] and an instrumented platform for in-situ monitoring [3; 4] of these emerging VPP processes have been developed. These tools offer spatiotemporally resolved insights into the unique and more complex process dynamics arising from the two-wavelength irradiance and the concurrent occurrence of two distinct reactions, along with their interactions. The new VPP_{2λ} process-structure-property relations are quantified using machine learning techniques applied to data from model simulations, in-situ monitoring, and ex-situ characterizations. Our preliminary results [5] demonstrate the potential advantage of the futuristic multi-wavelength VPP printing. This research is poised not only to advance VPP AM but also to contribute to the development and application of photochemistry and polymers. Furthermore, it holds promise for novel applications in multi-material 3D printing, including metamaterials, soft robots, and flexible electronics.

KEYWORDS

Vat photopolymerization; wavelength selective; photo inhibition; digital light processing; multi-material 3D printing; over-curing



This work is licensed under a Creative Commons Attribution 4.0 International License, which permits unrestricted use, distribution, and reproduction in any medium, provided the original work is properly cited.

Acknowledgment: The authors would like to thank Professor Sachin Velankar for his insightful discussion and suggestion on the VPP material development and characterization. The authors would also thank Dr. Chaitanya Vallabh for his help with the in-house VPP setup at Zhao's research lab.

Funding Statement: The authors acknowledge the fundings from the United States National Science Foundation, specifically from the Future Manufacturing program (Award: CMMI-2134447) and the Faculty Early Career Development program (CAREER Award: CMMI-2238557). Any opinions, findings, and conclusions or recommendations expressed in this publication are those of the authors and do not necessarily reflect the views of the National Science Foundation.

Conflicts of Interest: Xiayun Zhao reports on financial support provided by the United States National Science Foundation (Award: CMMI-2134447; and CAREER Award: CMMI-2238557).

Xiayun Zhao has a pending patent with US Application No.: 17/437,343. International Application No.: PCT/US20/21727. The reported photoinhibition aided vat photopolymerization-based additive manufacturing systems and methods along with some of the discussions have been filed within the pending patent above.

References

1. Zhang, H., Zhang, Y., Zhao, X. (2024). Vat photopolymerization additive manufacturing process modeling: a thermal-chemical coupling approach informed by in-situ and ex-situ characterization data. *Additive Manufacturing Letters*, 9.
2. Zhang, H., Zhao, X. (2022). In-situ thermal monitoring informed modeling and simulation of process temperature during vat photopolymerization additive manufacturing. *Materials Today: Proceedings*, 70, 237-241.
3. Zhang, Y., Zhang, H., Zhao, X. (2024). In-situ interferometric curing monitoring for digital light processing based vat photopolymerization additive manufacturing. *Additive Manufacturing*, 81, 104001.
4. Vallabh, C. K. P., Zhang, Y., Zhao, X. (2022). In-situ ultrasonic monitoring for Vat Photopolymerization. *Additive Manufacturing*, 55, 102801.
5. Zhang, Y., Bensouda, Y., Zhao, X. (2023). Enhancing Photopolymer Additive Manufacturing via Photoinhibition: An Initial Study. European Society for Precision Engineering and Nanotechnology (euspen) and American Society for Precision Engineering (ASPE) Joint Special Interest Meeting on Advancing Precision in Additive Manufacturing, KU Leuven, Belgium.



This work is licensed under a Creative Commons Attribution 4.0 International License, which permits unrestricted use, distribution, and reproduction in any medium, provided the original work is properly cited.